



**PATENT APPLICATION**

**RESPONSE UNDER 37 CFR §1.116  
EXPEDITED PROCEDURE  
TECHNOLOGY CENTER ART UNIT 2818**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re the Application of

Kiyoichi SUWA

Group Art Unit: 2818

Application No.: 09/729,339

Examiner: Q. Hoang

Filed: December 5, 2000

Docket No.: 108057

For: MASK, EXPOSURE METHOD, LINE WIDTH MEASURING METHOD, AND  
METHOD FOR MANUFACTURING SEMICONDUCTOR DEVICES

**AMENDMENT AFTER FINAL REJECTION UNDER 37 CFR §1.116**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**RECEIVED**

**FEB 23 2004**

Sir:

In reply to the August 27, 2003 Office Action, the shortened statutory period for reply  
being extended by the attached Petition for Extension of Time, please consider the following:

**Amendments to the Claims** as reflected in the listing of claims; and

**Remarks.**